Introduction to Nanophysics

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What is the size for a "nano"?

One (nm) equals to 1/1000000000 (10⁻⁹) meter

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10^{-3} m , Macro 10^{-6} m , Micro 10^{-9} m , Meso
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R. Feymann Already Knew about this!

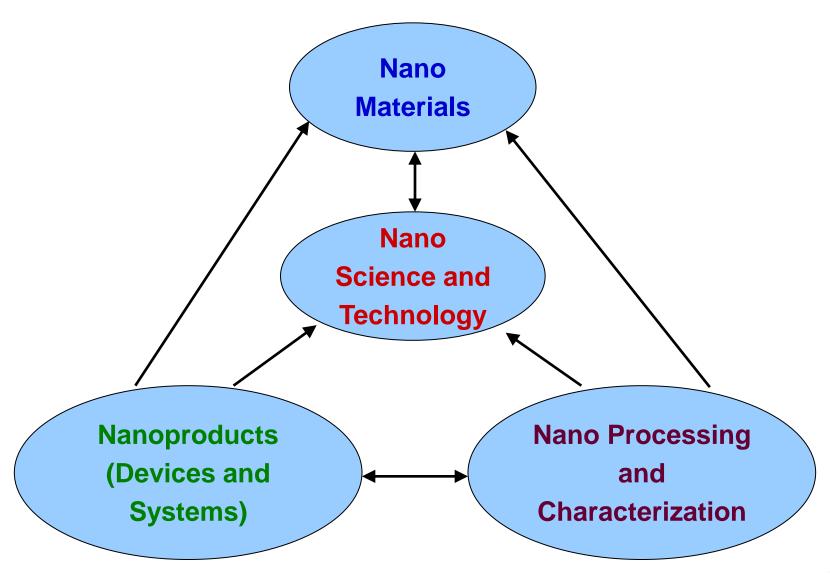


"There's plenty of room at the bottom!" in 1959.

Physicists noticed the "Nano" as early as

- 4th Century, Roman glassmaker: the color of glasses can be changed by mixing in metal particles
- In 1883, Films containing silver halides for photography were invented by George Eastman, founder of Koda.
- 1908, Gustay Mie first provided the explanation of the size dependence of color.
- Vision from Feynman in 1959: "There is plenty room at the bottom", and also recognized there are plenty of nature-given nanostructures in biological systems.
- 1950-1960, small metal particles were investigated by physicists.
- 1957, Ralph Landauer realized the importance of quantum mechanics plays in devices with small scales.
- Before 1997 => **mesoscopic** (or low dimensional) physics : quantum dots, wells, wires.....are known already.

Major Topics of Nanoscience and Technology



What is the Nano Technology?

Science and Technology Down scaling to size under 100 nm:

Via "Top-down" lithographic pattering:

- -- Moore's law!
- ➤ Manipulate the atomic and molecular structures:

"Bottom-up" nano materials, growth and assembly.

Feymann: There's plenty of room at the bottom

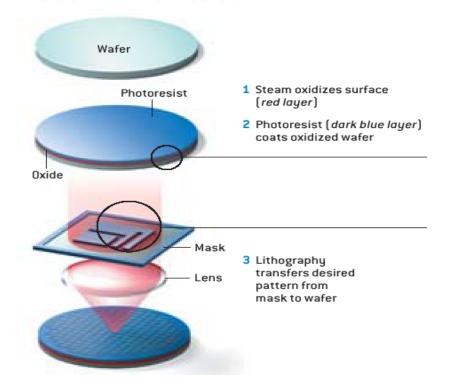
Major Driving Force pushing for Nano Technology: Due to the bottle neck in Microelectronics



Moore's Law:

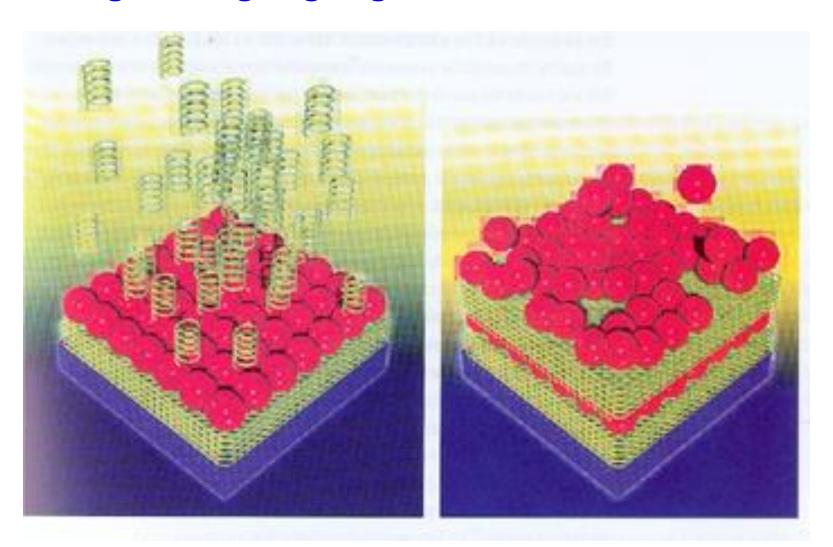
A 30% decrease in the size of printed dimensions in every two years.

BASIC CHIPMAKING PROCESS



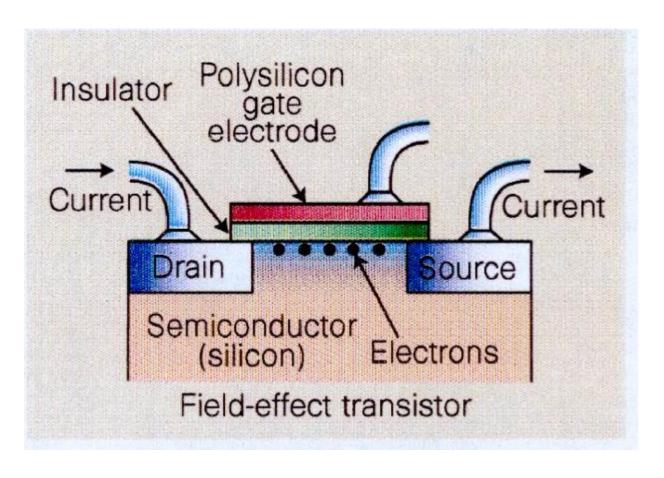
Bottom-up Nano systems & Self-Assembly

enabling of designing large molecules and nano materials



Two basic modern electronic technologies in Condensed Matter Physics Field

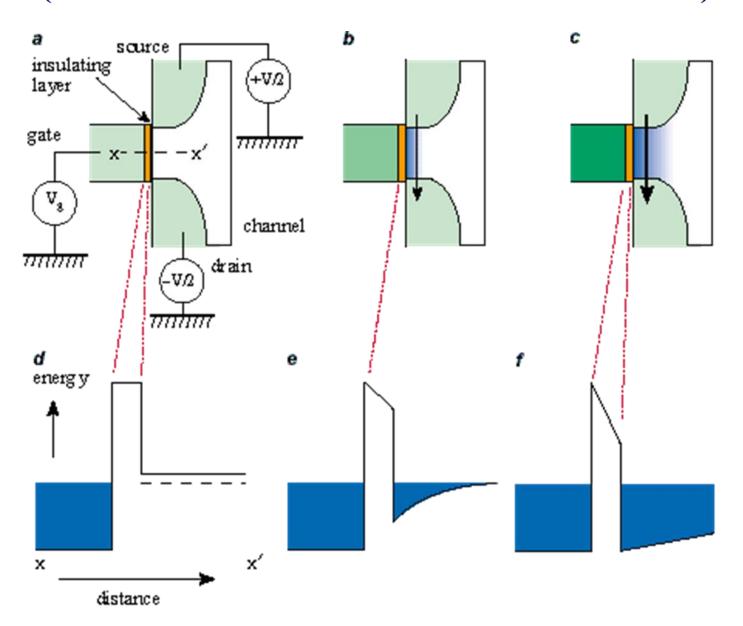
Metal-Oxide-Field Effect Transistor



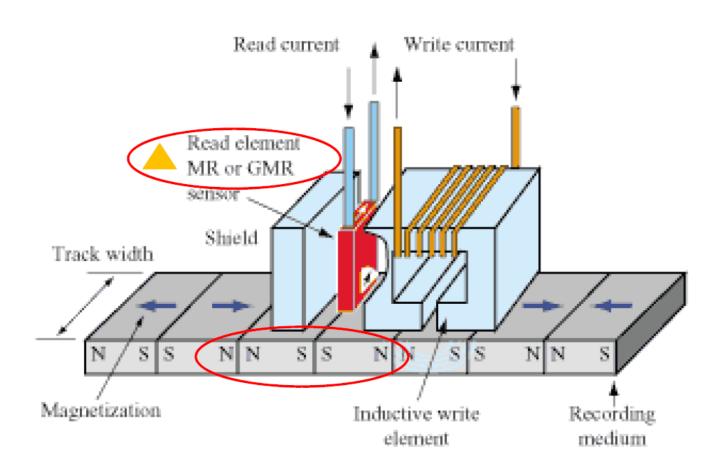
1960 Kahng and Atalla, First MOSFET 1970 First IC, 1 kbit, 750 khz microprocessor

電子科技之基礎--MOSFET

(metal-oxide-semiconductor field-effect transistor)



電子科技之基礎--磁記錄

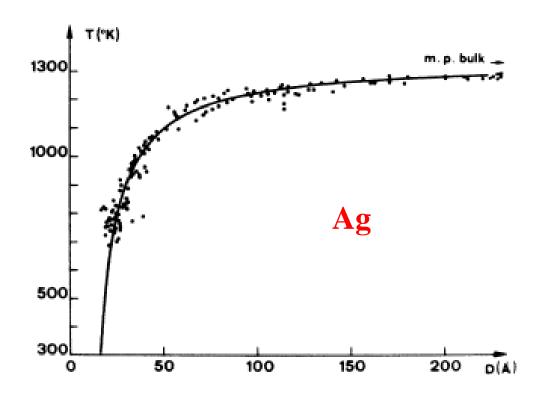


Five major lessons that we have learned

The First Lesson:

Bulk-to-nano Transition

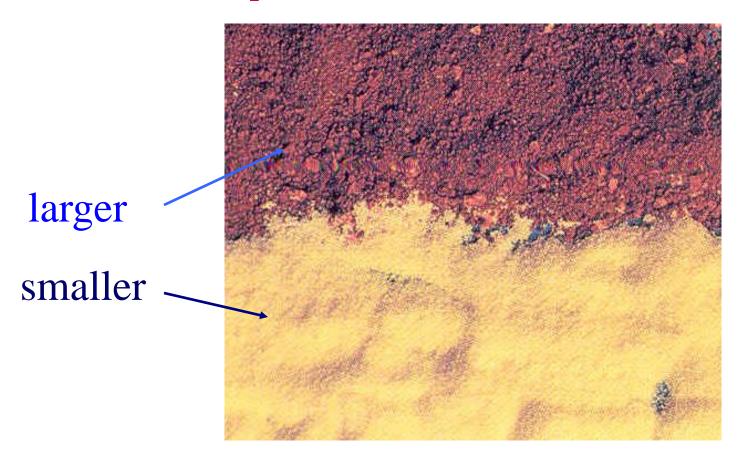
Ex: size-dependence of melting temperature



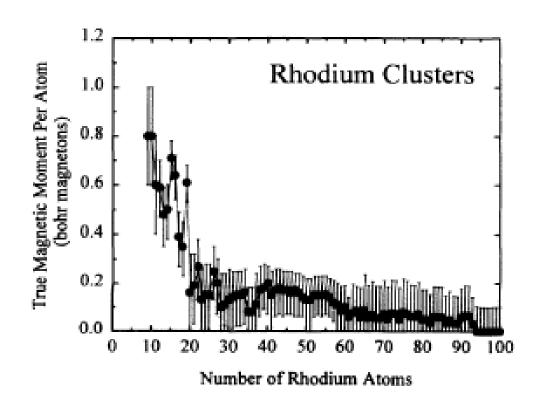
Ph. Buffat and J-P. Borel, Phys. Rev. A13, 2287 (1976)

Ex: size-dependence of color

powered cadmium selenide



Ex: size-dependence of magnetism



A. J. Cox et al. Phys. Rev. B49, 12295 (1994)

The Second Lesson: The Advent of Nano Era

• The ability of growing the nano scale materials and structures

• The ability of detecting and manipulating on the nano scale.

(I) Advance in thin film growth:

Such as Molecular Beam Epitaxy, atomic layer depostion, laser MBE, etc...

For nano electronics in metals, oxides, and semiconductors

(II) Detection at nano scale: STM, AFM, MFM, STEM, Cs-TEM

- In 1982, Binning, and Rohrer in IBM invented scanning tunneling microscope (STM).
- In 1986, Binning, Quate, and Gerber invented the atomic force microscope (AFM).

Integrated MBE Multi-chamber System



Now located in the Nano Technology Center, ITRI, Hsin Chu, Taiwan

For Metal, Oxide and Semiconductor Films On the Nano scale

Scanning Tunneling Microscope (STM)

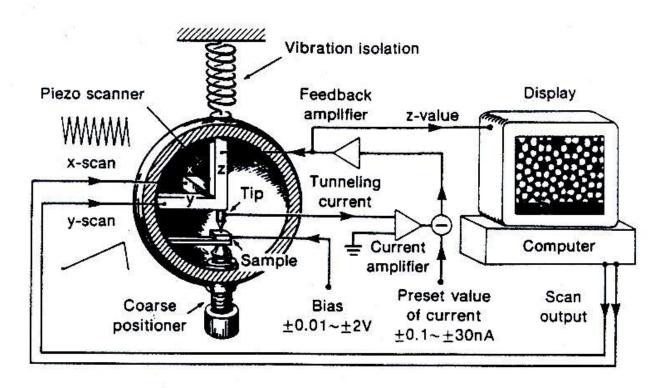
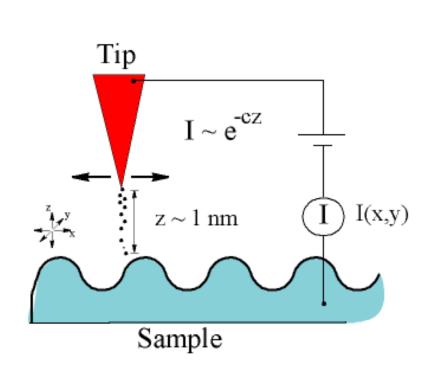
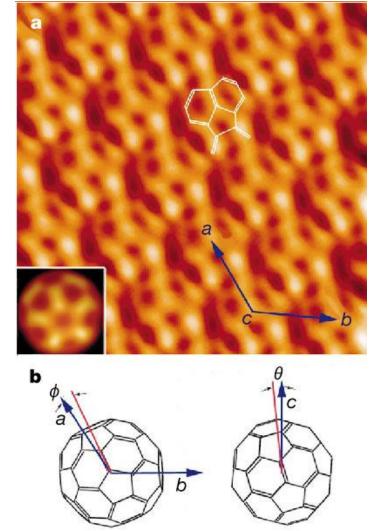


Figure 1.10 Scanning tunneling microscope. (From C. Julian Chen, Introduction to Scanning Tunneling Microscopy, Oxford: Oxford University Press, 1993.)

Scanning Tunneling Microscope (STM) – Physicist used to detect nano structures

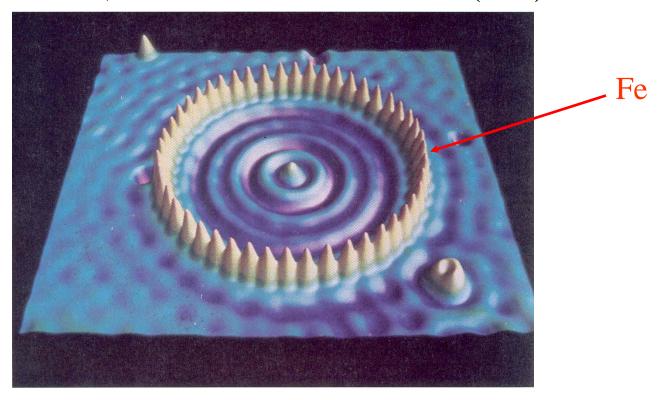


Nature 409, 304 (2001)



Quantum Corral

of 7.13 nm radius, 48 Fe atoms on the Cu (111) surface



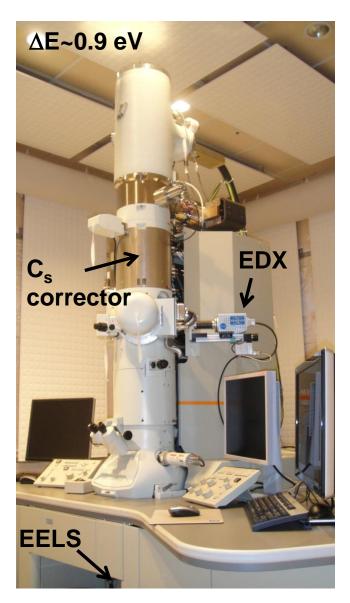
This STM image shows the direct observation of standing-wave patterns in the local density of states of the Cu(111) surface. These spatial oscillations are quantum mechanical interference patterns caused by scattering of the 2D electron gas off the Fe adatoms and point defects.

Scanning Transmission Electron Microscope Laboratory

2-Å STEM



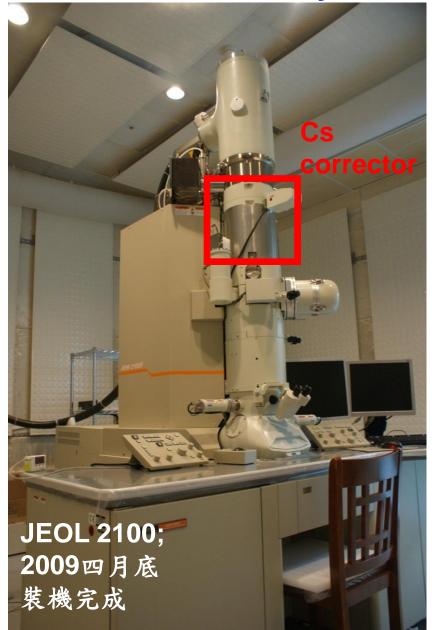
1-Å STEM

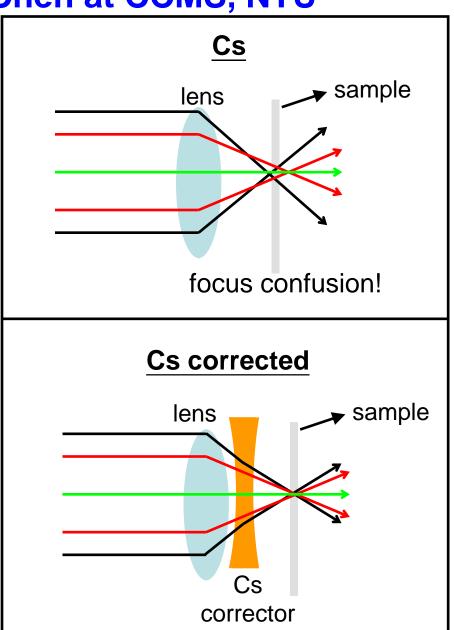


Prof. C. H. Chen and Dr. M.-W. Chu In CCMS/NTU.

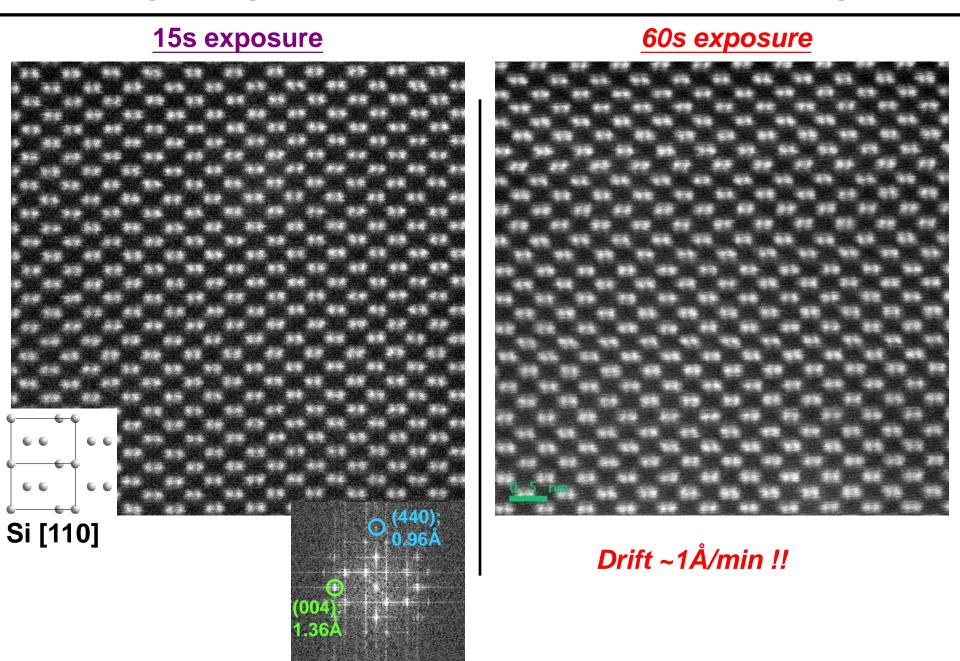
Spherical Aberration Corrected (球面相差)

Cs-STEM by C. H. Chen at CCMS, NTU

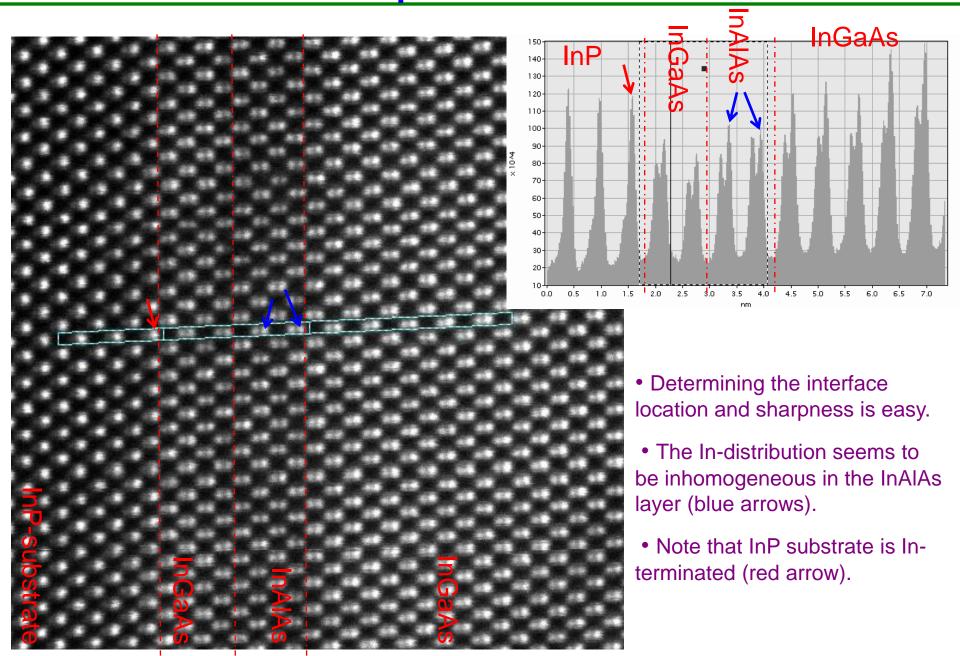




High-Angle ADF: Si dumbbell, 1.36 Å spacing

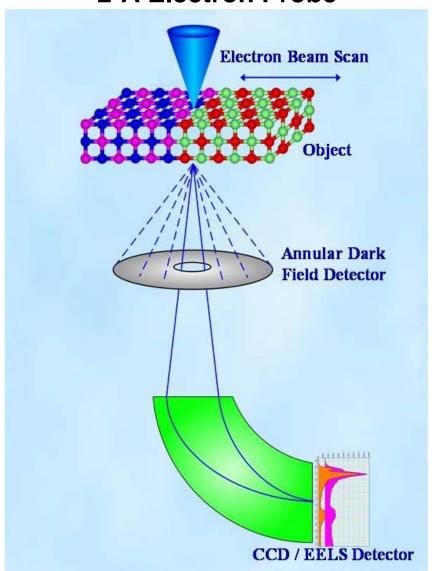


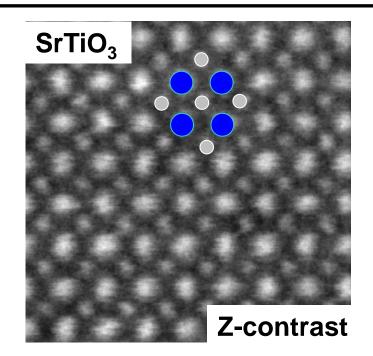
InGaAs/InAlAs superlattices on InP Substrate

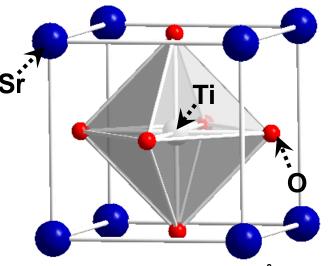


Atomic Resolution STEM Imaging: Z-contrast



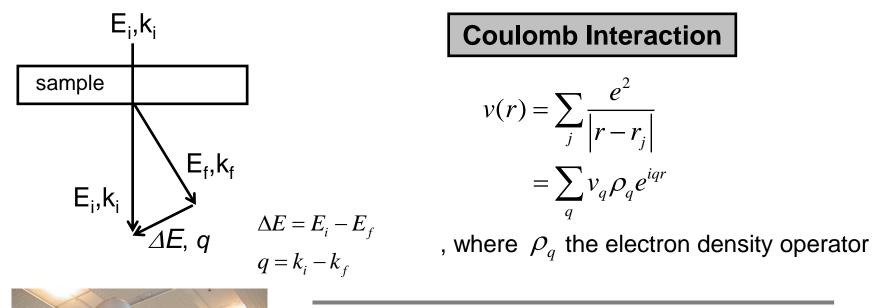






cubic; a = 3.905 Å

Electronic Exc.: Electron Energy-Loss Spectroscopy (EELS)



Coulomb Interaction

$$v(r) = \sum_{j} \frac{e^{2}}{|r - r_{j}|}$$
$$= \sum_{q} v_{q} \rho_{q} e^{iq}$$



Inelastic Scattering (△E) Probability

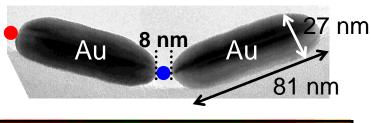
$$\frac{d^{2}\sigma}{d\Omega d\Box E} \sim \sum_{f} \left| \langle \psi_{f} | v(q) | \psi_{i} \rangle \right|^{2} \delta(E_{i} - E_{f} - \Delta E)$$

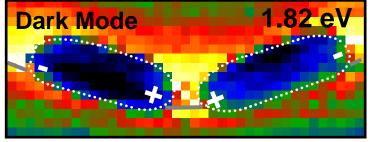
$$\sim \frac{1}{q^{4}} \cdot S(\omega, q) \longrightarrow \text{X-ray}$$

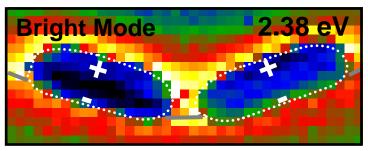
$$\sim \frac{1}{q^{2}} \cdot \text{Im} \left[\frac{1}{\varepsilon(\omega, q)} \right] \longrightarrow \text{EELS}$$

Spectral Imaging at Ultimate Spatial Resolution

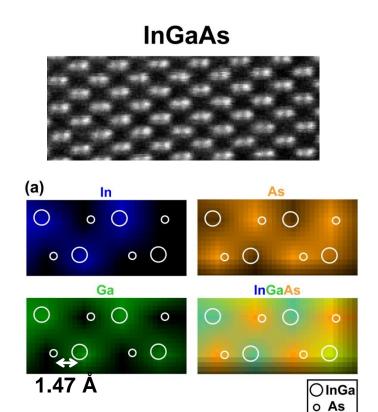
Plasmonic Mapping: STEM-EELS (2-Å Probe)







Chemical Mapping: STEM-EDX (1-Å Probe)



M.-W. Chu et al., Nano Lett. 9, 399 (2009).

M.-W. Chu et al., Phys. Rev. Lett. 104, 196101 (2010).

The Third Lesson: The importance of Quantum Physics

The cause for variation of scaling

- Influence of Boundary
 - -- Increase of proportion of boundaries
 - -- Existence of surface / edge modes
 - -- Geometrical reconstruction
- Decrease of the number of particles decrease of confinement, increase of purturbation
- Different scaling for different physical entity

Quantum Effect:

=> Most likely to have new breakthough!

The connection of materials wave

with mechanics

h = Planck constant

$$(6.626 \times 10^{-34} \text{ joule-sec})$$

DeBroglie: Einstein:
 $\lambda = h/p$ E=hv=p²/2m

Wave length

 $\lambda = h/p$

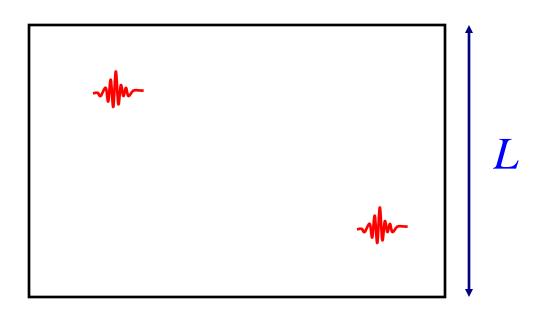
 $\lambda_{th}(300K) = 6.2nm$ Free electrons $10nm \le \lambda \le 100nm$ Semiconductors $(300K) \le 0.2nm$ **Atoms**

Bulk Limit



Nano Limit

Bulk materials λ << L



Nano λ~L

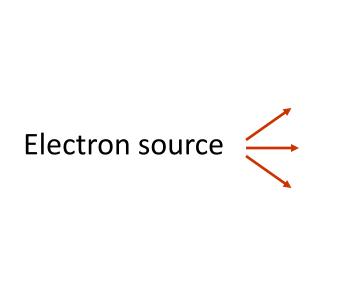


Major Qauntum Effect at the nano scale

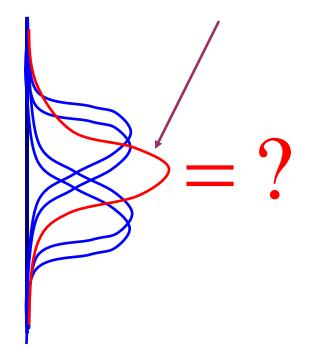
- Interference
- Quantization
- Tunneling
- Quantum Spin

(I) Interference

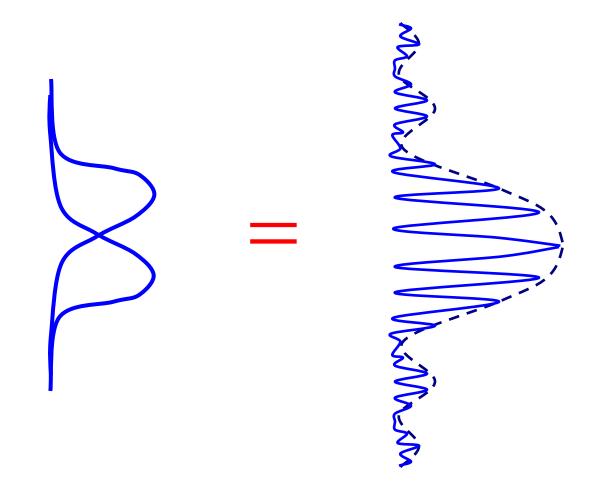
The wonder of electron in waves



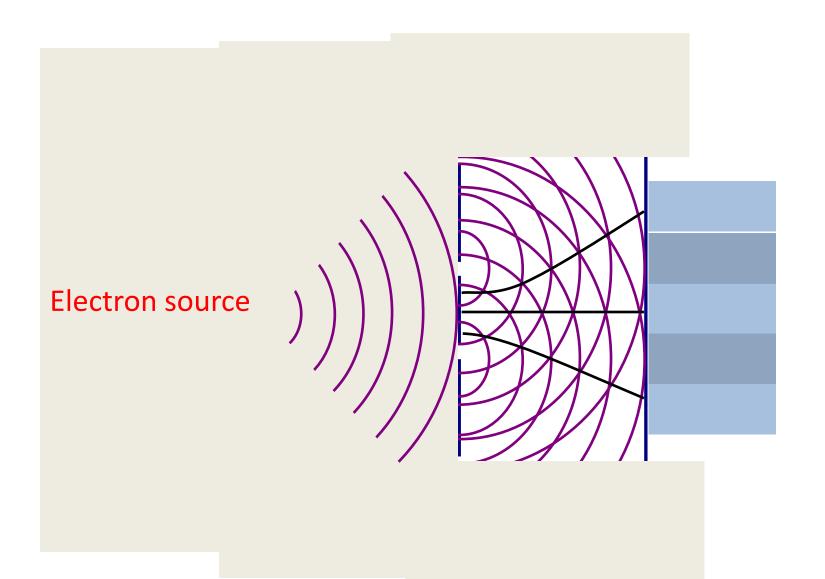
Classical mechanics

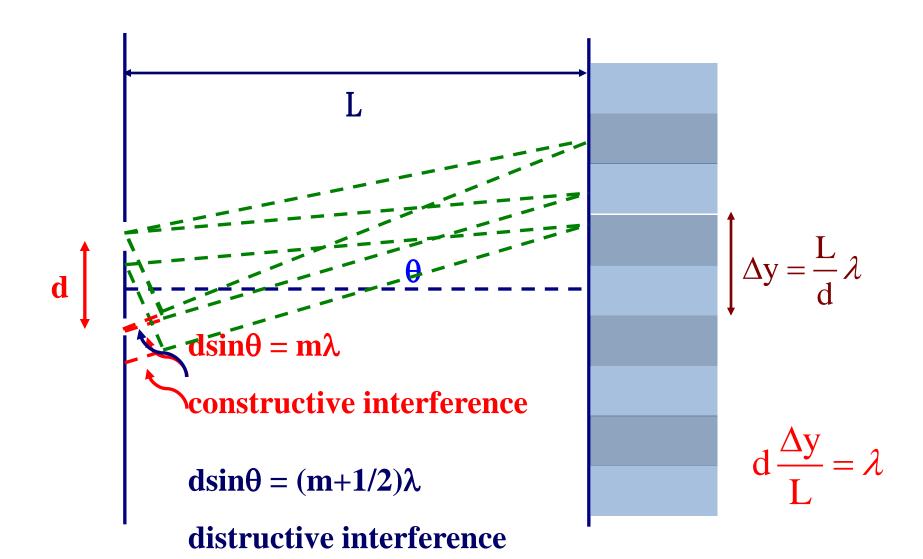


The wave property of electrons

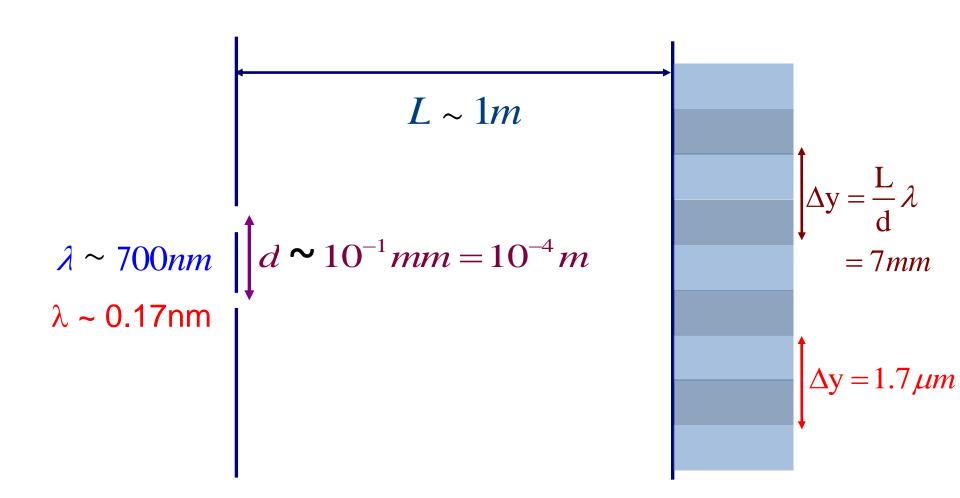


Double Slit Interference of Electrons





 \sim



(II) Quantization

Confinement of the materials wave



Standing Wave



Quantizations

The Qauntization of Energy

 $\delta E \propto 1/L^2$

$$n=3$$

$$L = \frac{n}{2}\lambda$$

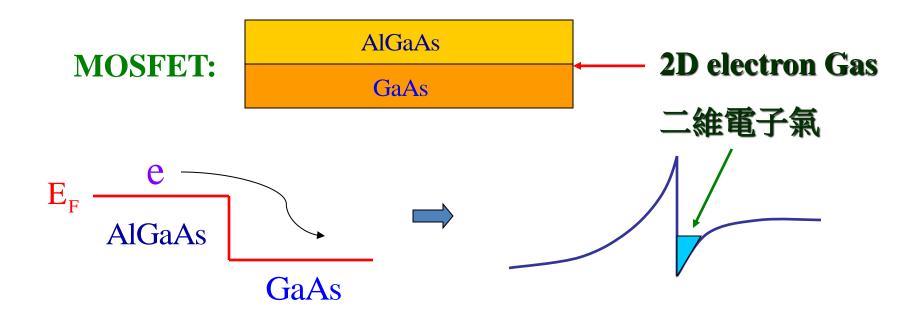
$$n=2$$

$$p = \frac{h}{\lambda} = \frac{nh}{2L}$$

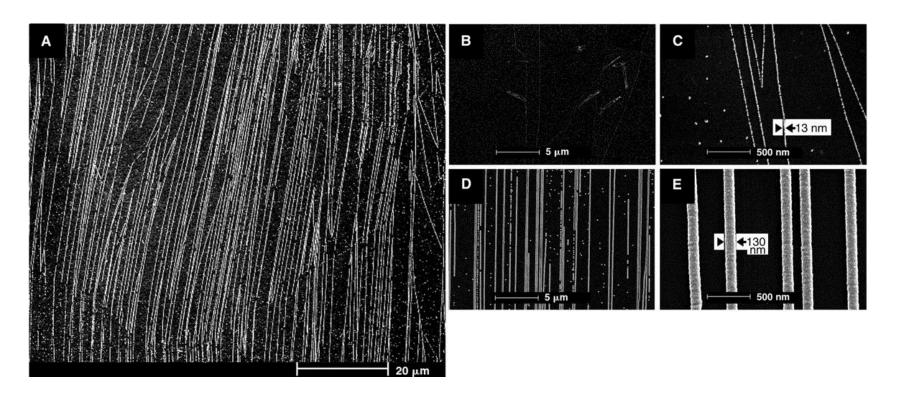
$$n=1$$

$$E_n = \frac{p^2}{2m} = \frac{n^2 h^2}{8mL^2}$$

Quantum well: 1D confinement

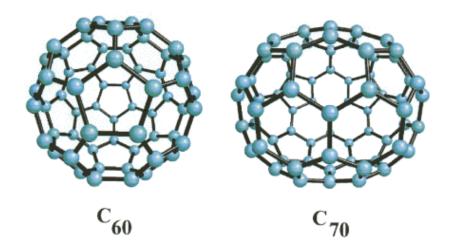


Quantum wire: 2 D-Confinement

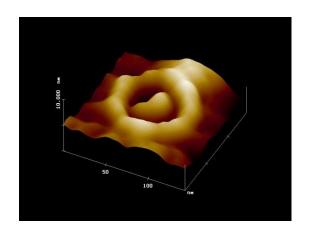


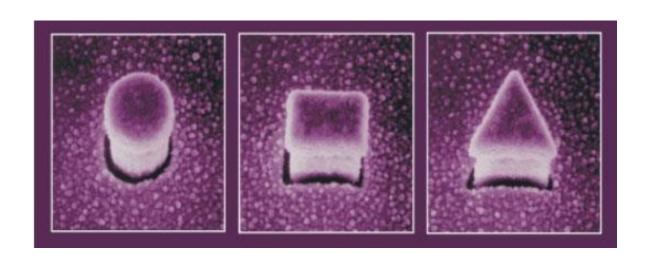
SEM images of MoO_x nanowires on graphite surfaces Science **290**, 2120-2123, (2000)

Quantum dot: 3 D - Confinement



Quantum Dots of various shape



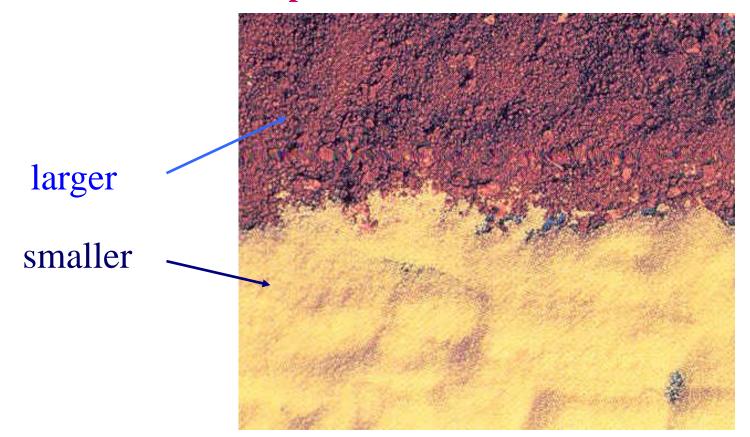


Absorption in scattering From red to yellow



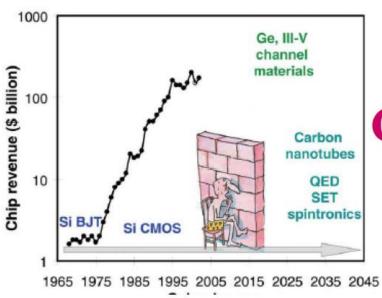
$$\frac{\lambda}{\lambda} \int E = hc/\lambda \propto 1/L^2$$

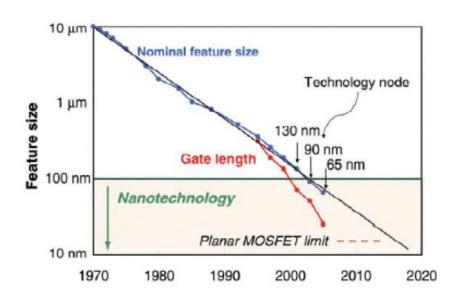
powdered Cadmium Selenide



Background for search new platform

Scaling limit of Si MOSFET & superparamagnetism





Carbon era?

Thompson and Parthasarathy, Materialstoday 9, 20, 2006

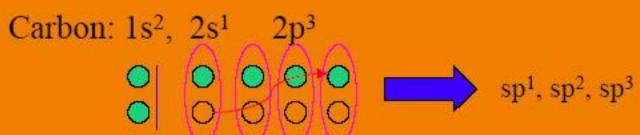
The Advent of Carbon Era?

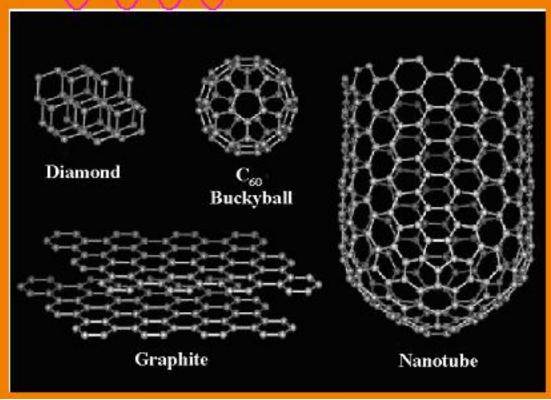
The Physics of Graphene:

- Possibility of relativistic electronics and spintronics

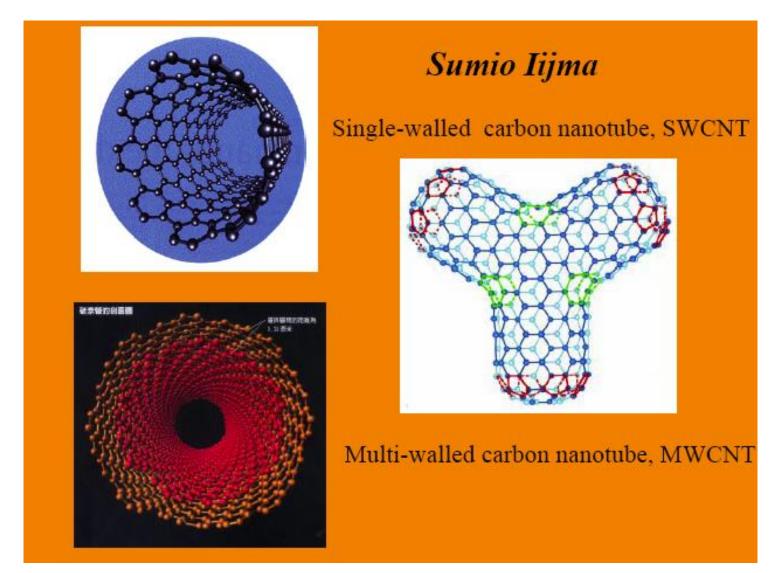
Carbon Nanotube

***** Structure of carbon nonatubes





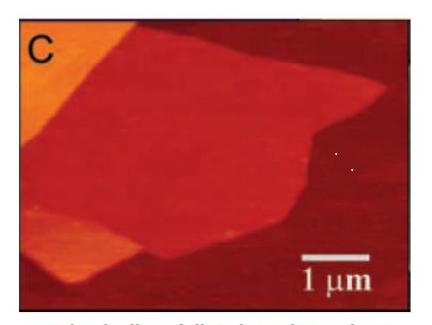
Carbon Nanotube

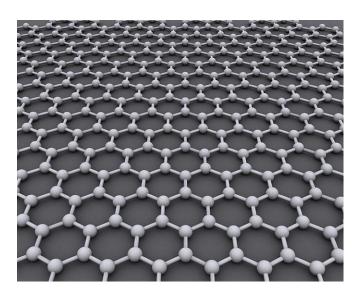


Carbon Nanotube based Transistors / Electronics

Unexpected realization of graphene sheet

(=

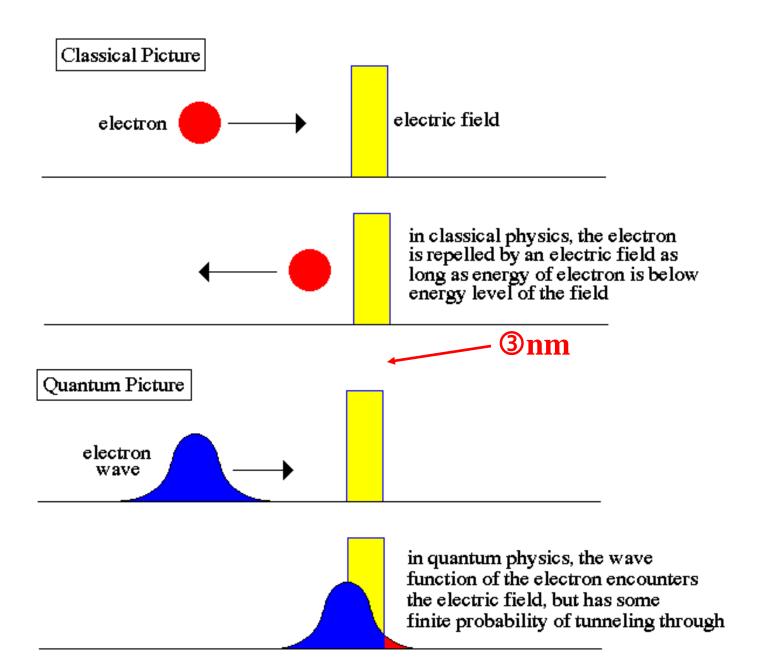




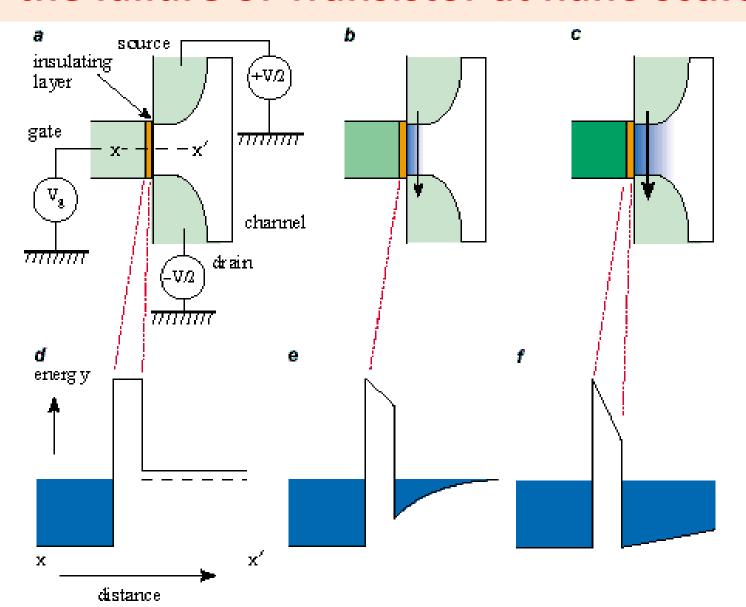
mechanically exfoliated graphene sheets

AFM image of single-layer graphene on SiO₂ K.S. Novoselove et al., Science 306, 666 (2004)

(III) Tunneling and Nano-electronics



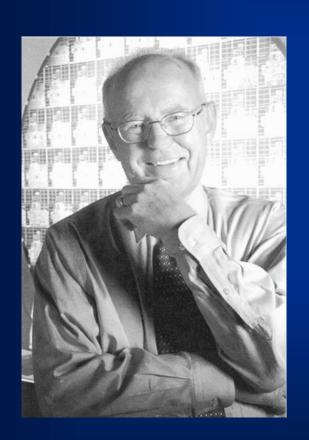
Quantum Tunneling is the major effect for the failure of Transistor at nano scale





近來大力推動奈米科技的背景

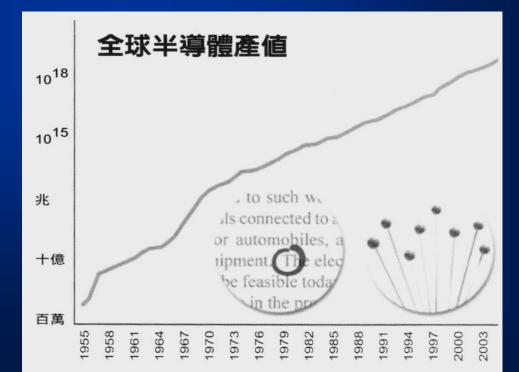
來自微電子學可能遭遇瓶頸的考慮



Moore's Law: 摩爾定律

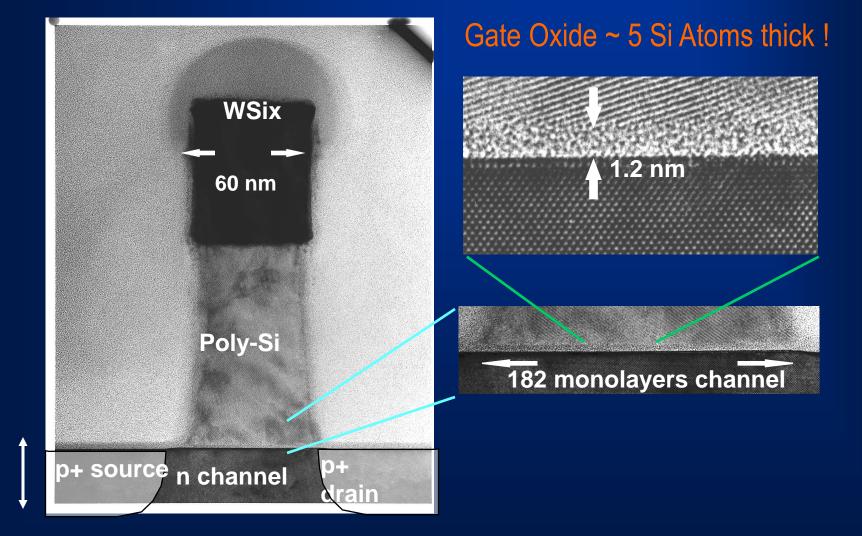
A 30% decrease in the size of printed dimensions every 1.5 years.

矽晶上電子原件數每1年半會增加一倍





Scaling Limits to CMOS Technology



Shrinking the junction depth increasing the carrier concentration



CMOS scaling, When do we stop?

Reliability: 25 22 18 16 Å

processing and yield issue

Tunneling: 15 Å

Design Issue: chosen for 1A/cm^2 leakage $I_{\text{on}}/I_{\text{off}} >> 1$ at 12 Å

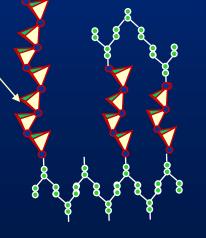
Bonding:

Fundamental Issues---

- how many atoms do we need to get bulk-like properties?
 EELS -- Minimal 4 atomic layers !!
- Is the interface electronically abrupt?
- Can we control roughness?

In 1997, a gate oxide was 25 silicon atoms thick.

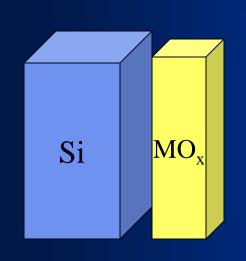
In 2007, a gate oxide will be 5 silicon atoms thick, if we still use SiO₂



and at least 2 of those 5 atoms will be at the interfaces.



Fundamental Materials Selection Guidelines



$$Si + MO_x \longrightarrow M + SiO_2$$

 $Si + MO_x \longrightarrow MSi_2 + SiO_2$
 $Si + MO_x \longrightarrow MSiO_x + SiO_2$

- Thermodynamic stability in contact with Si to 750℃ and higher. (Hubbard and Schlom) Alkaline earth oxide, IIIB, IVB oxide and rare earth oxide
- Dielectric constant, band gap, and conduction band offset
- Defect related leakage, substantially less than SiO_2 at $t_{eq} < 1.5$ nm
- Low interfacial state density $D_{it} < 10^{11} \, eV^{-1} cm^{-2}$
- Low oxygen diffusivity
- Crystallization temperature >1000°C

 t_{eq} : equivalent oxide thickness (EOT) to be under 1.0 nm $t_{eq} = t_{ox} \; \kappa_{\, SiO2} / \; \kappa_{ox}$



Basic Characteristics of Binary Oxide Dielectrics

Dielectrics	SiO ₂	Al_2O_3	Y_2O_3	HfO ₂	Ta_2O_5	ZrO_2	La ₂ O ₃	TiO_2
Dielectric constant	3.9	9.0	18	20	25	27	30	80
Band gap (eV) Band offset (eV)	9.0 3.2	8.8 2.5	5.5 2.3	5.7 1.5	4.5 1.0	7.8 1.4	4.3 2.3	3.0 1.2
Free energy of formation $MO_x + Si_2 \longrightarrow M + SiO_2$ @727C, Kcal/mole of MO _x	-	63.4	116.8	47.6	-52.5	42.3	98.5	7.5
Stability of amorphous phase	High	High	High	Low	Low	Low	High	High
Silicide formation?	-	Yes	Yes	Yes	Yes	Yes	Yes	Yes
Hydroxide formation?	-	Some	Yes	Some	Some	Some	Yes	Some
Oxygen diffusivity @950C (cm ² /sec)	2x 10 ⁻¹⁴	5x 10 ⁻²⁵	?	5	j	10 ⁻¹²	?	10 ⁻¹³



Integration Issues for High κ Gate Stack

FET Gate Stack

Gate Electrode

Upper Interface

Gate Dielectric

Lower Interface

Channel Layer

Si Substrate

Critical Integration Issues

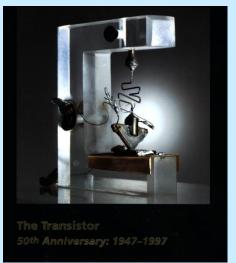
- Morphology dependence of leakage Amorphous vs crystalline films?
- Interfacial structures
- Thermal stability
- Gate electrode compatibility
- Reliability

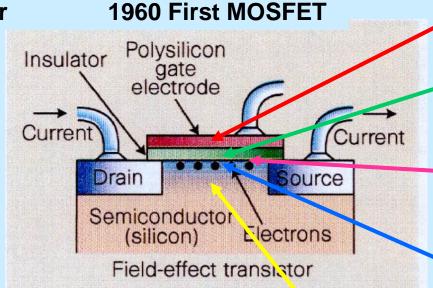
Fundamental Limitations

- Fixed charge
- Dopant depletion in poly-Si gate
- Dopant diffusion
- Increasing field in the channel region

Si CMOS Device Scaling – Beyond 22 nm node High κ, Metal gates, and High mobility channel

1947 First Transistor





Metal Gate

High κ gate dielectric

Oxide/semiconductor interface

High mobility channel

Moore's Law: The number of transistors per square inch doubles every 18 months

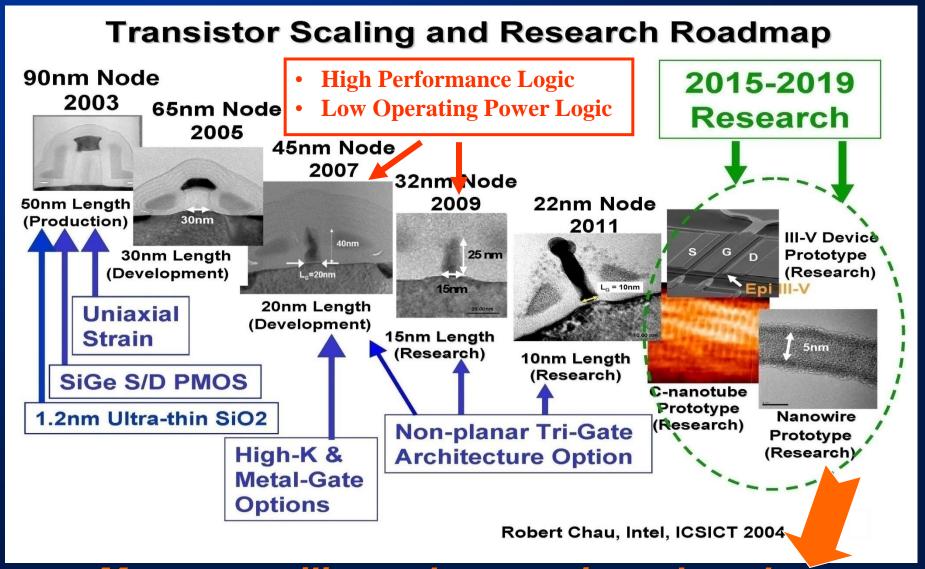
Integration of Ge, III-V with Si

Shorter gate length *L*Thinner gate dielectrics *t*_{ox}

Driving force:
High speed
Low power consumption
High package density

108Å GGG 5nm Ge

Thitel Transistor Scaling and Research Roadmap



More non-silicon elements introduced

Science and Technology of Ultimate CMOS

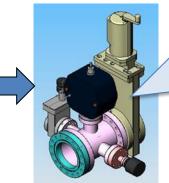
The Ultimate CMOS – End of road map

To achieve higher speed and lower power consumption

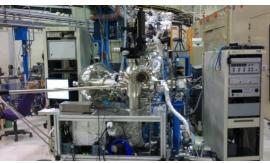
R&D of III-V InGaAs MOSFET state-of-art technology below 7 nm node, by combining advanced analysis of spectroscopy/microscopy/quantum transport/theoretical modeling



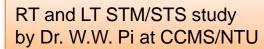
- In-situ ALD of oxide integrated with MBE
- Tailor reconstructed surface to be Ga-rich
- Controlled chemical reaction route and species



Portable UHV chamber for transfer 2"wafers in 3x10⁻¹⁰ torr for PES and STM analysis



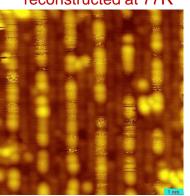
High resolution synchrotron radiation photoemission spectroscopy in NSRRC by Dr. T.W. Pi.



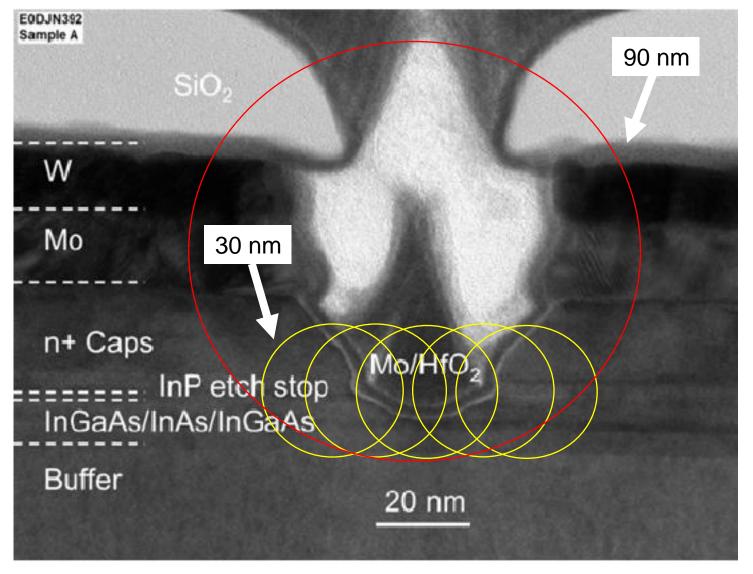




InGaAs surface reconstructed at 77K



Bragg Ptychography on III-V MOSFETs with gate length < 30 nm



J. A. Alamo et al., IEDM 24 (2013)

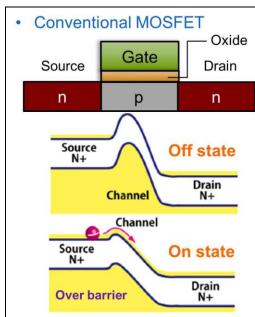
Tunneling-FETs offer sharper turn-on devices compared to MOSFETs

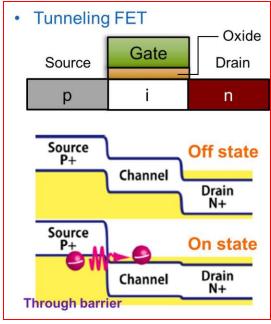
Lower VDD to lower switching energy ($P_{active} \sim C \cdot V_{DD^2}$)
Better performance for ultra low-power applications

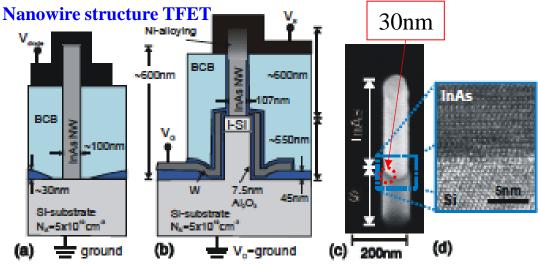
Atomic Model Prediction High mobility (III-V, SiGe) Ideal В TFET Drain current, log $l_{ m D}$ Bulk Si MOSFET MuG $S = 60 \text{ mV decade}^{-1}$ Gate voltage, V_c

A. M. Ionescu et al.,

Nature **479**, 329 (2011).





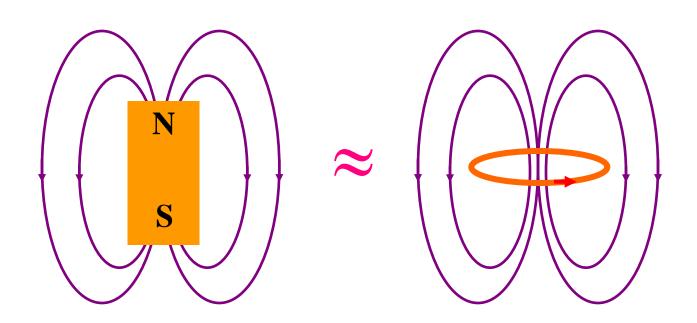


H. Riel et al., IEDM 391 (2012).

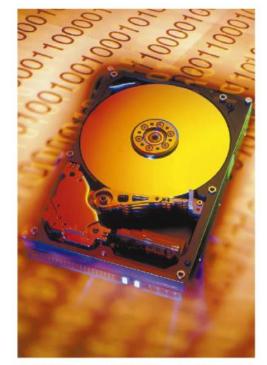
(IV) Quantum Spin

Spin and Nano technology

Electron Spin is the smallest unit of magnetism, came from Quantum Mechanics



Often being used for magnetic recording ~30 billion market

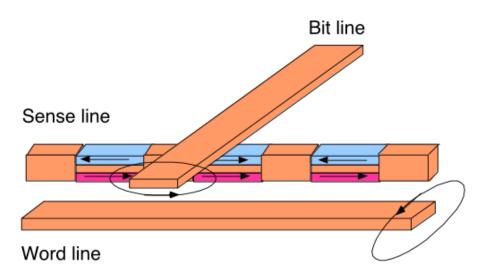


Well read: spintronics has dramatically increased data storage densities in hard drives.

Spintronics \Leftrightarrow Electronics

New generation of computer

Computation and storage in one shot



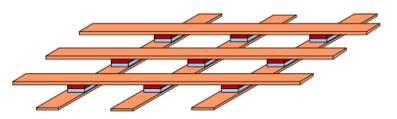
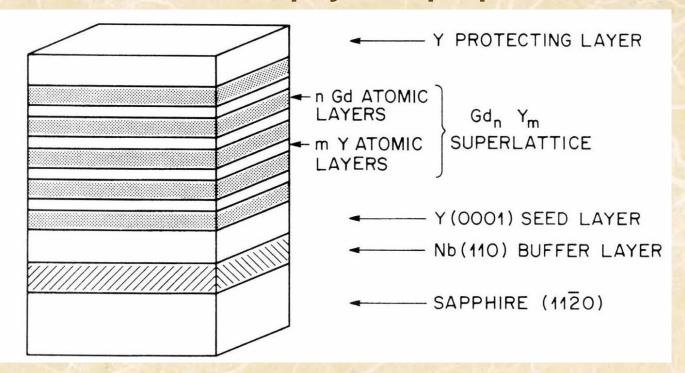


Fig. 7. A schematic representation of RAM that is constructed of magnetic tunnel junctions connected together in a point contact array. The conducting wires provide current to the junctions and permit voltage measurements to be made. They also enable the manipulation of the magnetization of the elements by carrying currents both above and below the magnetic junctions to create magnetic fields.

When turn-on, it is ready!

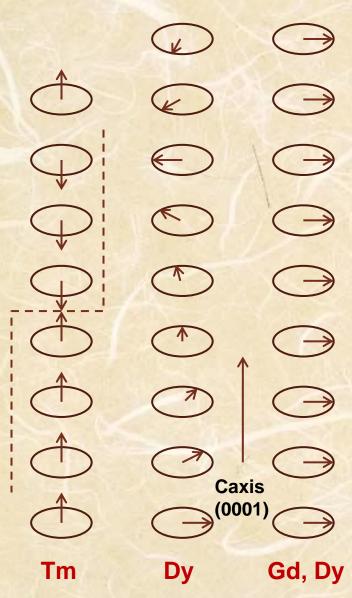
Artificial Superlattice

--- Matching the structural periodicity with physical length scale of superconductivity and magnetism -- Modulation of physical properties



Invention of metal molecular beam epitaxy in 1981

-- Single crystal epitaxial superlattices with Atomically abrupt interfaces

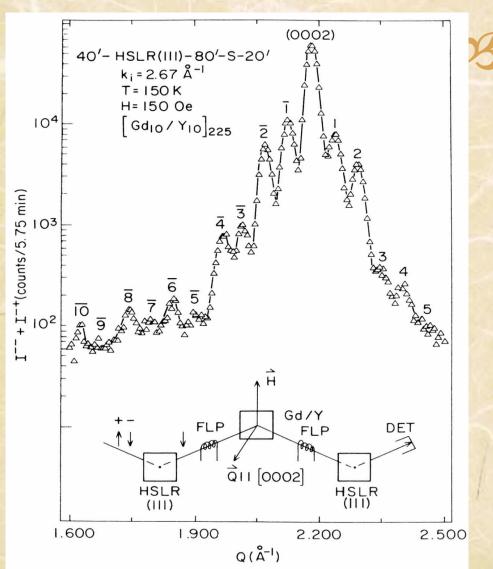


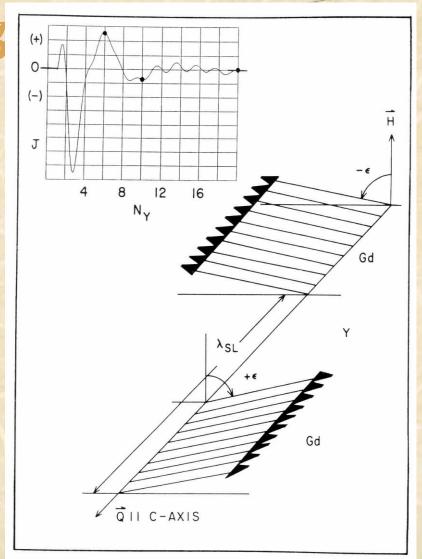
HCP crystal structure

- Similar crystal- chemical nature of rare earth forms coherent superlattices
- Metallic superlattice effect
 - Long range nature of the indirect exchange interaction
 - Magnetic coupling of magnetic rare earth through non – magnetic Y, Lu
 - Modulation of magnetic properties of Gd - Y Superlattices
 - Spin structure modification of Tm Y,
 Dy Y Superlattices
- 2-dimensional magnetism
- Interfacial magnetism

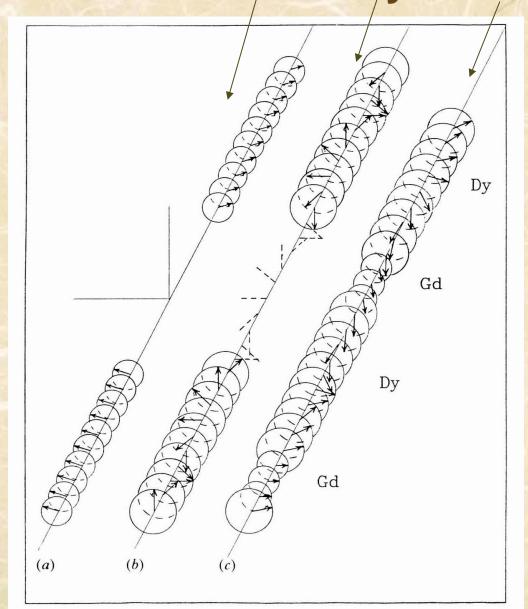
Spin structures of heavy rare - earths

Neutron Diffraction Studies of the Gd₅-Y₁₀ Magnetic Superlattice – Antiferromagnetically coupled





Spin Structure Tailoring in artificial Superlattices Gd-Y Dy-Y Gd-Dy



Giant Magnetoresistance(GMR)

What is GMR?

- **GMR** is a very large change in electrical resistance that is observed in a ferromagnet/paramagnet multilayer structure.
- Resistance change occurs when the relative orientations of the magnetic moments in alternate ferromagnetic layers change as a function of applied field.

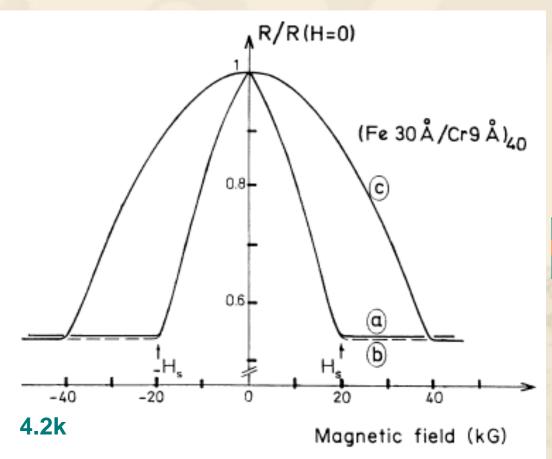
The total resistance of this material is lowest when the magnetic orientations of the ferromagnetic layers are aligned, is highest when the orientations are anti-aligned.

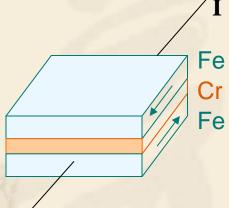
Para.
Ferro.
Para.
Ferro.
Para.
Ferro.
Para.
Ferro.
Para.
Ferro.

Ferro.

M. N. Baibich, J. M. Broto, A. Fert, F. Nguyen Van Dau, and F. Petroff, *Phys. Rev. Lett.*, **61**, 2472 (1988).

First Evidence of GMR





Hs corresponds to the field at which all layer magnetizations point along the field direction.

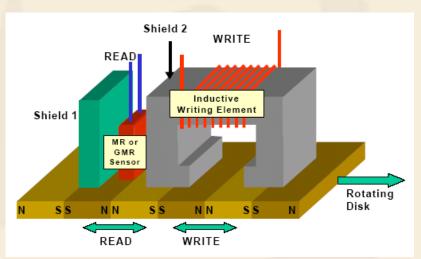
Spin-Valve GMR

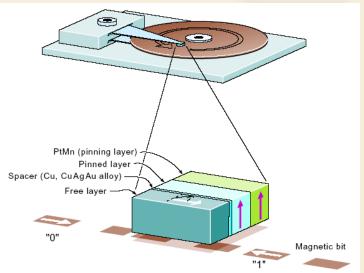
← The simple structure of Spin-valve GMR is



The magnetisation of the top permalloy layer is free to rotate as the field is varied. Second permalloy layer is fixed due to its exchange interaction with the iron-manganese layer.

GMR Spin Valve Reading Head

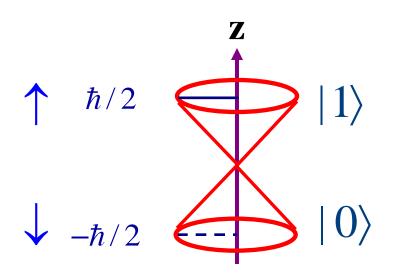




- ♣ Magnetization is stored as a "0" in one direction and as a "1" in the other. This is the magnetic field sensed by the GMR head.
- When the head passes over these magnetic bits, the magnetization direction of the free layer in the head responds to the field in each bit by rotating either up or down.
- The resulting change in the resistance is sensed by the voltage across the GMR head (current passing through the GMR element is constant).

Quantum behavior of ferromagnets

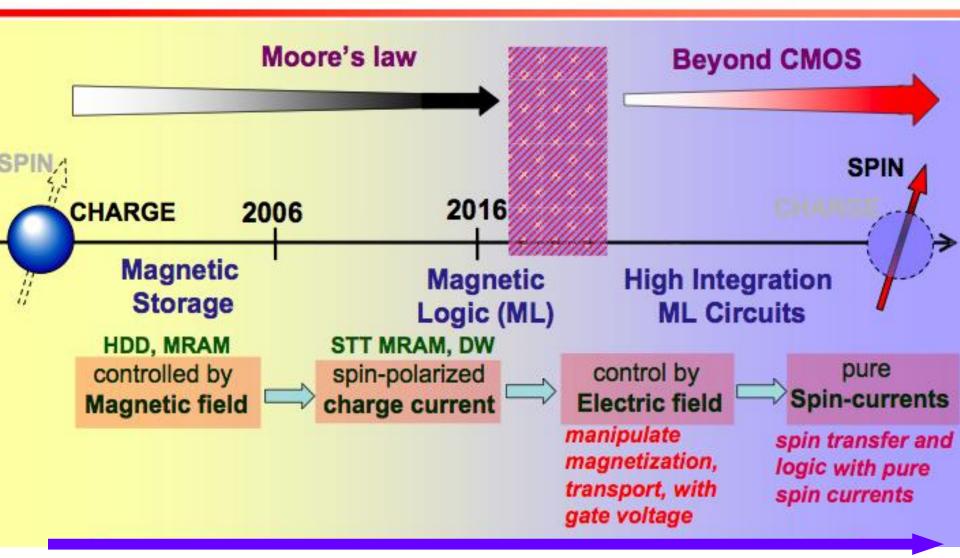
-Spin as a quantum qubit



$$qubit = \alpha | 0 \rangle + \beta | 1 \rangle$$

Due to superposition More information!

Tentative roadmap



Can we take the "charge" out of Spintronics ? To generate pure spin current!

Courtesy Claude Channert Université Paris Su INTERMAG 2008 Madrid Spain

Spintronics vs Electronics

- ✓ Reducing the heat generated in traditional electronics is a major driving force for developing spintronics.
- ✓ Spin-based transistors do not strictly rely on the raising or lowering of electrostatic barriers, hence it may overcome scaling limits in charge-based transistors.
- ✓ Spin transport in semiconductors may lead to dissipationless transfer of information by pure spin currents.
- ✓ Allow computer speed and power consumption to move beyond limitations of current technologies.

Reliable generation of pure spin currents!

- ✓ Spin Hall effect (2004)
- ✓ Spin Pumping (2006)
- ✓ Inverse Spin Hall effect (2006)
- ✓ Spin Seebeck effect (2008)
- ✓ Spin Caloritronics (2010)

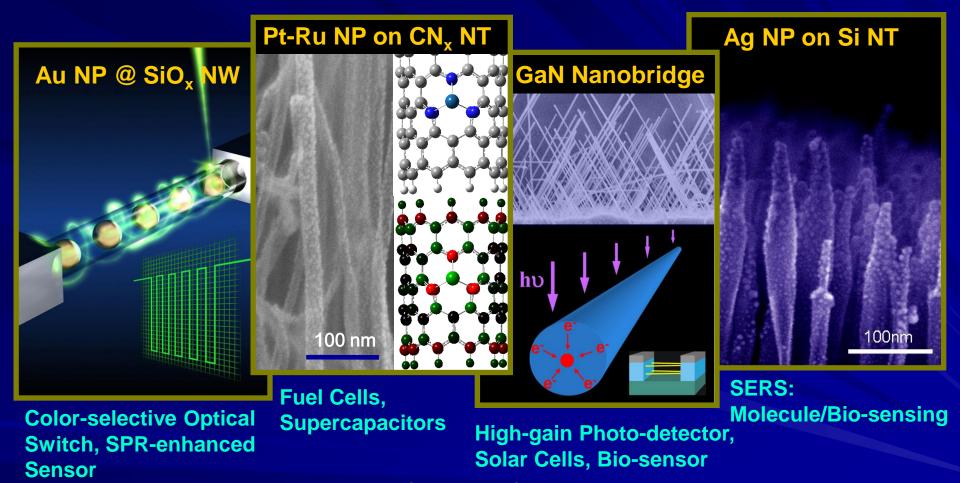
Major Qauntum Effect at the nano scale

- Interference
- Quantization
- Tunneling
- Quantum Spin

The Fourth Lesson:

Innovations of
nano structures and
nano materials
for various applications

Overview of Advanced Materials Laboratory



Li-Chyong Chen

Center for Condensed Matter Sciences
National Taiwan University

The Nano-world at CCMS-AML:

a Fruitful Research Field with Technology Implications

JACS 123, 2791 (2001)

APL 81, 22 (2002)

JACS 127, 2820 (2005)

APL 88, 241905 (2006)

APL 90, 213104 (2007)

Adv. Func. Mater. 18, 938 (2008)

Small 4, 925 (2008)

Analytical Chem. 81, 36 (2009)

APL 79, 3179 (2001)

APL 81, 4189 (2002)

Adv. Func. Mater. 12, 687 (2002)

APL 86, 203119 (2005)

Chem. Mater. 17, 3749 (2005)

JACS 128, 8368 (2006)

PRB 75, 195429 (2007)

JACS 130, 3543 (2008)

Chapter 9, pp. 259-309,

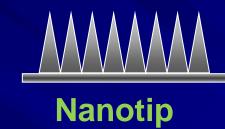
Nanowires and nanobelts, Z.L.

Wang Ed., Kluwer (2004)

Adv. Func. Mater. 16, 537 (2006)

APL 90, 123109 (2007)

Adv. Mater. 19, 4524 (2007)



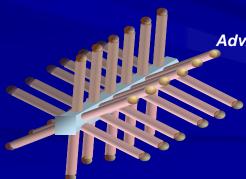
APL 83, 1420 (2003) Nano. Lett. 4, 471 (2004) Chem. Mater. 17, 553 (2005) Adv. Func. Mater. 15, 783 (2005) APL 86, 203119 (2005) US Patent 6,960,528,B2 APL 89, 143105 (2006) Nature Nanotech. 2, 170 (2007)

Nano Lett. 9, 1839 (2009)



Core-shell

APL 81, 1312 (2002) Nano. Lett. 3, 537 (2003)



Brush

Adv. Func. Mater. 14, 233 (2004)

Other Thin Films: APL 86, 21911 (2005) APL 86, 83104 (2005) APL 86, 161901 (2005) APL 87, 261915 (2005) JVST B 24, 87 (2006) APL 88, 73515 (2006) Adv. Mater. 21, 759 (2009)

Adv. Mater. 14, 1847 (2002) Nature Mater. 5, 102 (2006)

Peapod

Belt

Wire/Rod

Tube

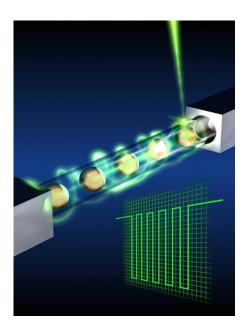
A Color-selective Nanoswitch

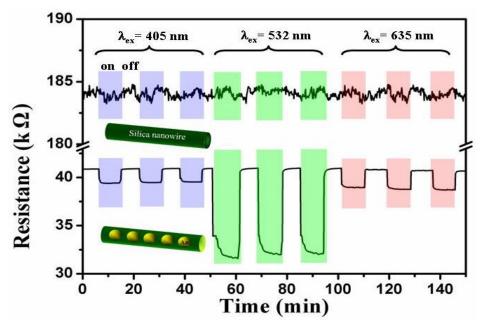
Photosensitive Gold Nanoparticle-embedded Dielectric Nanowires

M. S. Hu, et al., Nature Materials 5, 102-106 (2006)

A Fast Breaking Paper

(in each individual field, only 1 was selected bimonthly among the Highly Cited Papers) (http://esi-topics.com/fbp/2007/august07-Li-ChyongChen.html)





In ancient Arabian story of "Ali Baba and the Forty Thieves", the treasure is in a cave, of which the mouth is sealed by magic. It opens on the words "Open Sesame" and seals itself on the words "Close Sesame".

The nanopeapod (i.e., gold nanoparticle-embedded dielectric nanowire) will open to green light but shut for lights of other colors.

Si Nanotips-Array and their Hetero-junctions: On-chip, IC-compatible

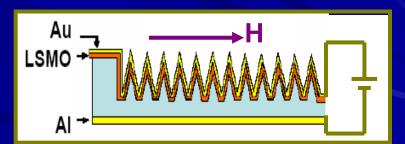
- * Antireflection:
 - Broadband (uv-terahertz), Omnidirectional (>70°)
- * Electroluminescence in ZnO/SiNTs:
 - IR emission, x10 higher; turn-on ~3V, x2 lower than film
- * Magneto-resistance in LSMO/SiNTs:
 - Room-temp. MR at lower bias and magnetic field



Nature-Nanotechnology 2 (2007) 770



Nano Letters 9 (2009) 1839



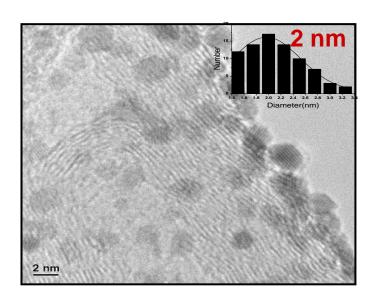
Promising high-density memory: On-going

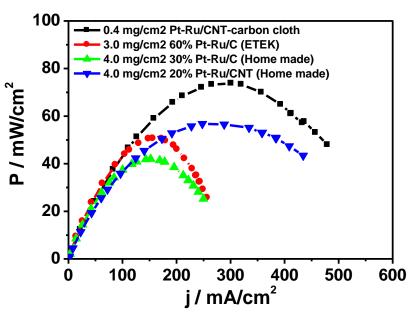
Next-generation Energy Solution (I): Fuel Cell with Low-loading of Precious Metals

Ultrafine Pt Nanoparticles Uniformly Dispersed on Arrayed Carbon Nanotubes with High Electrochemical Activity at Low Loading of Precious Metal

C. L. Sun, et al., Chemistry of Materials 17, 3749-3753 (2005)

C. H. Wang, et al., J. Power Sources 171, 55-62 (2007)



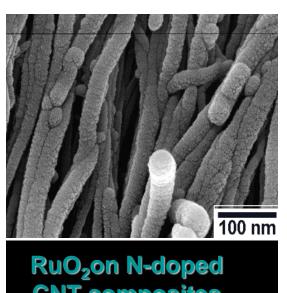


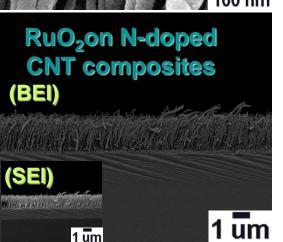
- Direct methanol fuel cell is promising power generator with a wide range of applications from portable electronic devices to automobiles.
- Nanotubes-Pt/Ru composites are highly efficient in loading precious metals. Only **one tenth** of metal loading, in comparison to the conventional, is needed.

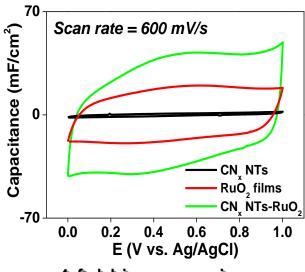
Next-generation Energy Solution (II): High-performance Supercapacitor

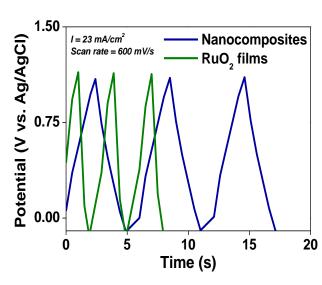
Ultrafast Charging-discharging Capacitive Property of RuO₂ Nanoparticles on Carbon Nanotubes Using Nitrogen Incorporation

W. C. Fang, et al., Electrochemistry Communications 9, 239-244 (2007) W. C. Fang, et al., J. Electrochemical Society 155, K15-K18 (2008)









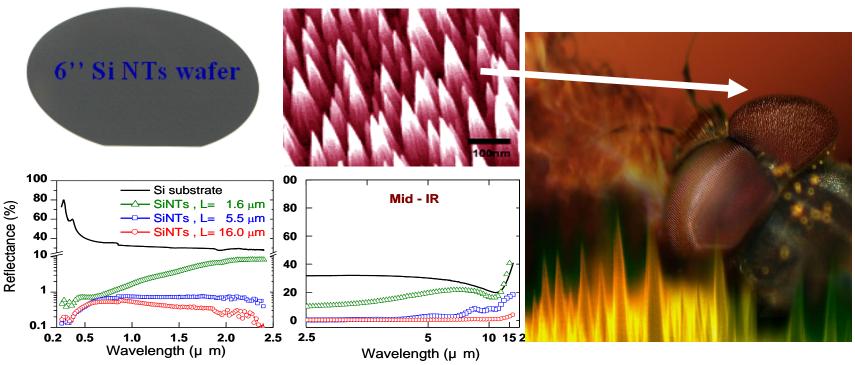
- 4 fold increase in capacitance
- Optimal capacitance of 1380 F/g at 600 mV/s (theory: 1450 F/g)
- Output current as high as 23 mA/cm²
- Stable at high scan rate
- 10 fold increase in charge-discharge rate

A Man-made Moth Eye

Broadband and Quasi-omni-directional Anti-reflection Properties with Biomimetic Silicon Nanostructure

Y. F. Huang, et al., Nature Nanotechnology 2, 770-774 (2007) & US Patent 2005

Featured by NPG Asia Materials, March 2008

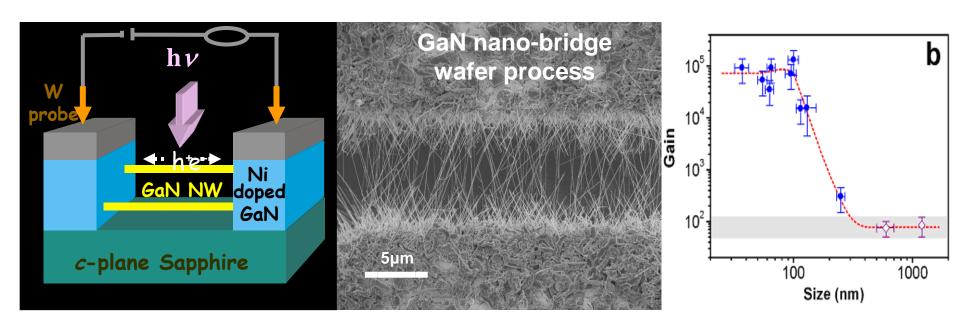


Many plants and animals have tiny surface structures that absorb certain wavelengths of light. These naturally formed nanostructures provide the colors in butterfly wings, camouflage for cicadas and enable moths to capture as much light as possible when flying at night. Now, we have created nanostructure surfaces which mimic moth eye and surpass its function in anti-reflection in that they absorb almost all incident light.

Building a Nano-scale Bridge On-chip

On-chip Fabrication of Well Aligned and Contact Barrier-Free GaN Nanobridge Devices with Ultrahigh Photocurrent Responsivity

R. S. Chen, et al., Small 4, 925-929 (2008)



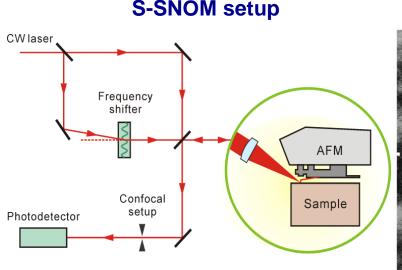
- Nanowire: Naturally formed core-shell structure, 1D electron gas-like property
- On-chip process for building GaN nanobridge devices, which provide a large surface area, short transport path, and high responsivity for next-generation sensors and detectors

The Fifth Lesson:

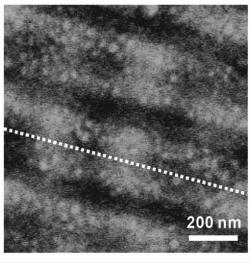
Nano photonics
and
Bio-applications

Nano-photonics and Plasmonics Near-field examination of blue-ray discs

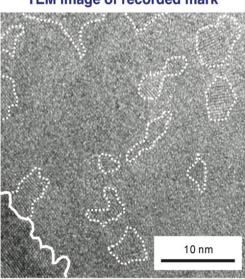
Dr. Juen-Kai Wang, CCMS, NTU



Near-field image of recorded disc



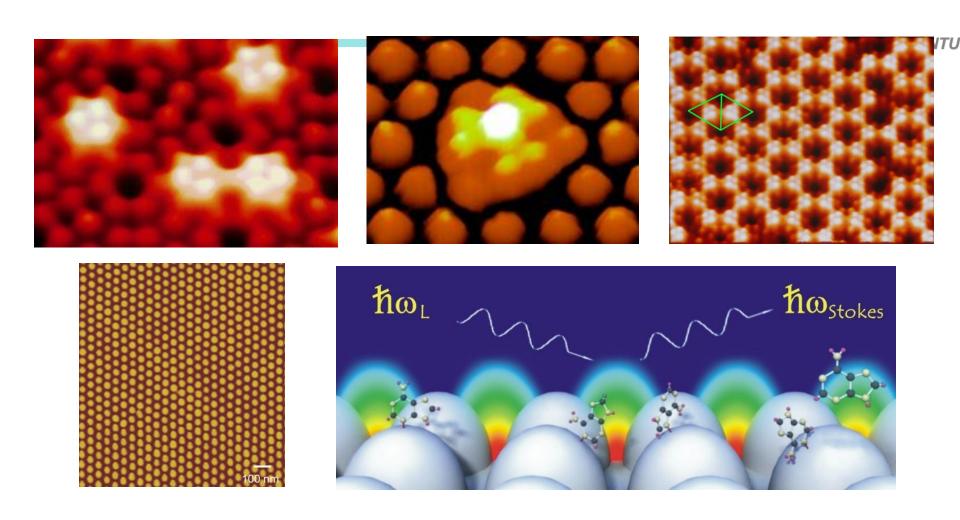
TEM image of recorded mark



- Scattering-type SNOM reveals sub-10 nm optical signature.
- The optical contrasts of the dark and the bright regions in near-field image of phasechange layer correspond to amorphous and polycrystalline AgInSbTe, respectively.
- Small bright spots with a size of ~30 nm emerge within the dark region, corresponding to the nano-sized ordered domains in the TEM image.
- s-SNOM provides a direct optical probe in nanometer scale for high density optical storage media.

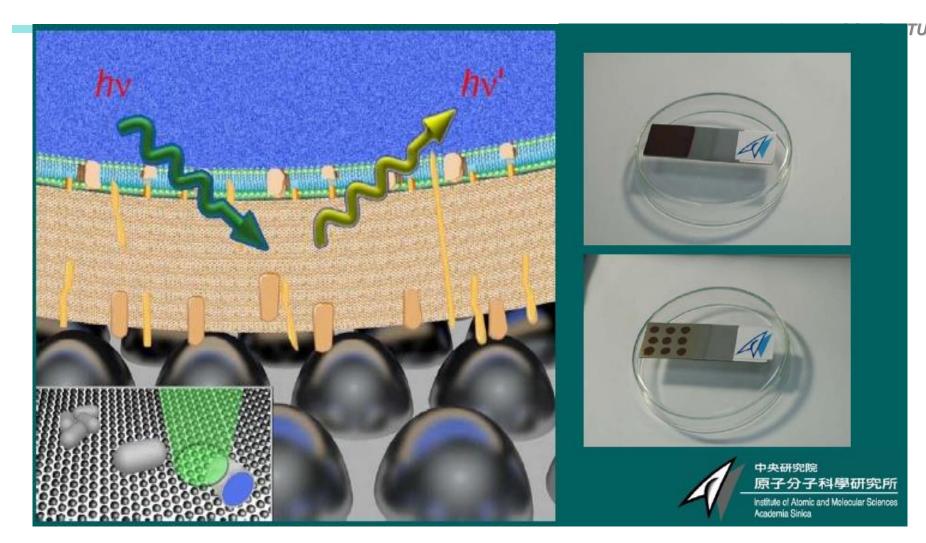
J. Y. Chu et al., Appl. Phys. Lett. 95, 103105 (2009).

Creating Monodispersed Ordered Arrays of Surface-Magic-Clusters and Anodic Alumia Nanochannels by Constrained Self-organization



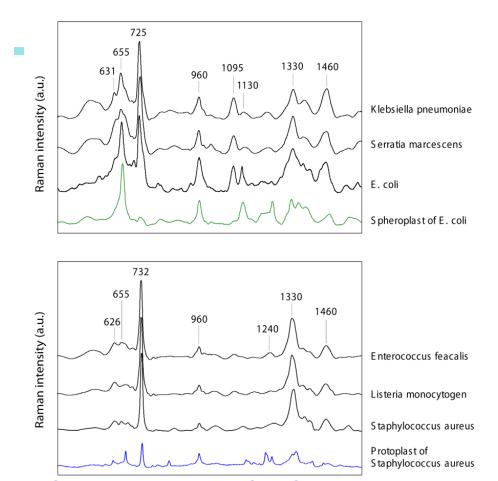
Prof. Yuh-Lin Wang 王玉麟 IAMS Academia Sinica, Taiwan

A High Sensitivity and High Speed Biomedical Diagnostic Technology using SERS

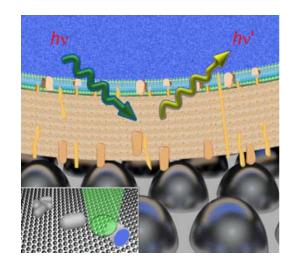


Prof. Yuh-Lin Wang 王玉麟 IAMS Academia Sinica, Taiwan

SERS detection of bacterial cell wall



Dr. Juen-Kai Wang, CCMS, NTU



- Sensitive and stable SERS profiles based on our substrates readily reflect different bacterial cell walls found in Gram-positive, Gram-negative, and mycobacteria group.
- Characteristic changes in SERS profile are recognized in the drug-sensitive bacteria of antibiotic exposure, which could be used to differentiate them from the drug-resistant ones.

Papers to read

- "Observation of a Magnetic Antiphase Domain Structure with Long-Range Order in a Synthetic Gd-Y Superlattice", C. F. Majkrzak, J. W. Cable, J. Kwo, M. Hong, D. B. McWhan, Y. Yafet, J. V. Waszczak, and C. Vettier, Phys. Rev. Lett. 56, 2700, (1986).
- M. N. Baibich, J. M. Broto, A. Fert, F. Nguyen Van Dau, F. Petroff, *Phys. Rev. Lett.*,
 61, 2472 (1988).
- "High k gate dielectrics Gd₂O₃ and Y₂O₃ for Si", J. Kwo*, M. Hong, A.R. Kortan, K. T. Queeney, Y. J. Chabal, J. P. Mannaerts, T. Boone, J. J. Krajewski, A. M. Sergent, and J. M. Rosamilia, Appl. Phys. Lett, 77, 130, (2000).
- "Epitaxial Cubic Gd₂O₃ as a Dielectric for GaAs Passivation", M. Hong, J. Kwo, A. R. Kortan, J. P. Mannaerts, and A. M. Sergent, Science, 283, 1897, (1999).
- "Observation of the Spin Hall Effect in Semiconductors", Y. K. Kato, R. C. Myers, A.
 C. Gossard, D. D. Awschalom*, Science 306, 1910 (2004).
- "Tunnel field-effect transistors as energy-efficient electronic switches", A. M. Ionescu, and H. Riel, Nature, 479, 329 (2011).